
PULSED LASER DEPOSITION OF THIN FILMS

APPLICATIONS-LED GROWTH OF FUNCTIONAL MATERIALS

Edited by

Robert Eason

Optoelectronics Research Centre
University of Southampton, UK



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Dedication

I would like to dedicate this book to my mother, Mrs. Helena Eason, and to my daughters, Katie Alice, Emily Beth, and Jessica Rosanna. I do not know if they are devotees of PLD and all its varied possibilities, but if not, then there is always time to change track, I believe.

I would further like to thank all the authors for their patience and resilience in the face of adversity, and the editorial time dilation phenomenon that has somehow extended the due date for publication.

Mea culpa to all.

Finally, many thanks to Doug Chrisey who was an editor on PLD1 and with whom I have had many discussions concerning PLD2. Although in the end he does not appear as a co-editor, in the early stages he was a guiding light in steering this book to completion. Doug, many thanks.

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